

FEB 26 2009

Application No. 10/717,975  
Amendment dated February 26, 2009  
Reply to Office Action of August 27, 2008

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Docket No.: 51200(70329)

**AMENDMENTS TO THE CLAIMS**

Claims 1-21. (cancelled)

Claim 22. (currently amended) A method for forming a photoresist relief image comprising:

- a) applying an organic underlayer composition coating layer on a substrate, the underlayer composition comprising (i) a first resin that comprises phenol groups; (ii) a second acrylate resin that is distinct from the first resin and comprises one or more anthracene groups; (iii) a crosslinker component that is distinct from the first resin and second resin, the crosslinker comprising a benzoquanamine compound or a melamine compound; and (iv) an acid or acid generator compound;
- b) applying a positive-acting photoresist composition coating layer over the underlayer composition, the photoresist composition comprising a photoactive component and one or more resins that comprise Si groups, phenolic groups and photoacid-labile groups; and
- c) exposing the photoresist layer to radiation having a wavelength of about 248 nm.

Claims 23-67. (cancelled)

Claim 68. (previously presented) The method of claim 22 wherein the crosslinker component comprises a benzoquanamine compound.

Claim 69. (previously presented) The method of claim 22 wherein the crosslinker component comprises a melamine compound.

Claims 70-71. (cancelled)

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